

10/722,032

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(FILE 'HOME' ENTERED AT 11:32:49 ON 11 MAY 2005)

FILE 'BIOSIS, MEDLINE, CAPLUS, WPIDS, USPATFULL' ENTERED AT 11:34:05 ON  
11 MAY 2005

L1 184 S ARRAY AND CHAMBERS AND FLOW CELLS  
L2 141 S L1 AND SUPPORT  
L3 96 S L2 AND INLET  
L4 92 S L3 AND OUTLET  
L5 77 S L4 AND CHEMICAL  
L6 18 S L5 AND SUPPORT? (6A) CHAMBER?  
L7 18 DUP REM L6 (0 DUPLICATES REMOVED)

=> s 15 and array (15a) polymer?

L8 6 L5 AND ARRAY (15A) POLYMER?

=> dup rem 18

PROCESSING COMPLETED FOR L8

L9 6 DUP REM L8 (0 DUPLICATES REMOVED)

=> d 19 bib abs 1-6

L9 ANSWER 1 OF 6 USPATFULL on STN  
AN 2004:165271 USPATFULL  
TI Method and apparatus for synthesis of arrays of DNA probes  
IN Cerrina, Francesco, Madison, WI, UNITED STATES  
PI US 2004126757 A1 20040701  
AI US 2002-62967 A1 20020131 (10)  
DT Utility  
FS APPLICATION  
LREP QUARLES & BRADY LLP, 411 E. WISCONSIN AVENUE, SUITE 2040, MILWAUKEE, WI,  
53202-4497  
CLMN Number of Claims: 24  
ECL Exemplary Claim: 1  
DRWN 17 Drawing Page(s)  
LN.CNT 916  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
AB The present invention provides an apparatus and method for constructing  
arrays of DNA sequences using the image of a micromirror **array**  
projected on a reaction site using projection optics where the  
projection optics have insufficient resolution to fully resolve the  
separation between mirrors of the mirror **array**.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L9 ANSWER 2 OF 6 USPATFULL on STN  
AN 2004:138760 USPATFULL  
TI Substrate preparation process  
IN Goldberg, Martin, Saratoga, CA, UNITED STATES  
Diggelman, Martin, Nierdorf, SWITZERLAND  
Hubbell, Earl, Mountain View, CA, UNITED STATES  
McGall, Glenn, San Jose, CA, UNITED STATES  
Ngo, Nam Quoc, Campbell, CA, UNITED STATES  
Morris, MacDonald, Felton, CA, UNITED STATES  
Yamamoto, Mel, Fremont, CA, UNITED STATES  
Tan, Jennifer, Newark, CA, UNITED STATES  
Rava, Richard P., Redwood City, CA, UNITED STATES  
PA Affymetrix, Inc., Santa Clara, CA, UNITED STATES, 95051 (U.S.  
corporation)  
PI US 2004105932 A1 20040603  
AI US 2003-722032 A1 20031125 (10)  
RLI Continuation of Ser. No. US 2000-716507, filed on 20 Nov 2000, GRANTED,  
Pat. No. US 6706875 Continuation of Ser. No. US 1999-244568, filed on 4  
Feb 1999, GRANTED, Pat. No. US 6307042 Continuation of Ser. No. US  
1996-634053, filed on 17 Apr 1996, GRANTED, Pat. No. US 5959098  
DT Utility

FS APPLICATION  
LREP BANNER & WITCOFF LTD., ATTORNEYS FOR AFFYMETRIX, 1001 G STREET , N.W.,  
ELEVENTH FLOOR, WASHINGTON, DC, 20001-4597  
CLMN Number of Claims: 49  
ECL Exemplary Claim: 1  
DRWN 20 Drawing Page(s)  
LN.CNT 2233

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB The present invention provides novel processes for the large scale preparation of arrays of **polymer** sequences wherein each **array** includes a plurality of different, positionally distinct **polymer** sequences having known monomer sequences. The methods of the invention combine high throughput process steps with high resolution photolithographic techniques in the manufacture of polymer arrays.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L9 ANSWER 3 OF 6 USPATFULL on STN  
AN 2004:66011 USPATFULL  
TI Substrate preparation process  
IN Goldberg, Martin, San Jose, CA, United States  
Diggelman, Martin, Arlesheim, SWITZERLAND  
Hubbell, Earl, Mountain View, CA, United States  
McGall, Glenn, Mountain View, CA, United States  
Ngo, Nam Quoc, Campbell, CA, United States  
Morris, MacDonald, San Jose, CA, United States  
Yamamoto, Mel, Fremont, CA, United States  
Tan, Jennifer, Newark, CA, United States  
Rava, Richard P., San Jose, CA, United States  
PA Affymetrix, Inc., Santa Clara, CA, United States (U.S. corporation)  
PI US 6706875 B1 20040316  
AI US 2000-716507 20001120 (9)  
RLI Continuation of Ser. No. US 1999-244568, filed on 4 Feb 1999, now patented, Pat. No. US 6307042 Continuation of Ser. No. US 1996-634053, filed on 17 Apr 1996, now patented, Pat. No. US 5959098  
DT Utility  
FS GRANTED  
EXNAM Primary Examiner: Riley, Jezia  
LREP Banner & Witcoff, Ltd.  
CLMN Number of Claims: 52  
ECL Exemplary Claim: 1  
DRWN 22 Drawing Figure(s); 20 Drawing Page(s)  
LN.CNT 2189

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB The present invention provides novel processes for the large scale preparation of arrays of **polymer** sequences wherein each **array** includes a plurality of different, positionally distinct **polymer** sequences having known monomer sequences The methods of the invention combine high throughput process steps with high resolution photolithographic techniques in the manufacture of polymer arrays.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L9 ANSWER 4 OF 6 USPATFULL on STN  
AN 2003:172874 USPATFULL  
TI **Chambers** for storing arrays  
IN Hilson, Richard O., Sunnyvale, CA, UNITED STATES  
Peck, Bill J., Mountain View, CA, UNITED STATES  
Leproust, Eric M., Campbell, CA, UNITED STATES  
PI US 2003118718 A1 20030626  
US 6858186 B2 20050222  
AI US 2001-35907 A1 20011224 (10)  
DT Utility  
FS APPLICATION  
LREP AGILENT TECHNOLOGIES, INC., Legal Department, DL429, Intellectual Property Administration, P. O. Box 7599, Loveland, CO, 80537-0599  
CLMN Number of Claims: 39  
ECL Exemplary Claim: 1

DRWN 3 Drawing Page(s)

LN.CNT 1513

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB Apparatus and methods are disclosed for storing a plurality of supports having a plurality of **chemical** compounds bound to the surfaces of the supports. In the apparatus, a mechanism for diffusively introducing pressurized gas into the apparatus is in fluid communication with an **outlet** element comprising a plurality of openings. A holding chamber for the supports is in fluid communication with the **outlet** element. The **outlet** element and the holding chamber are disposed such that gas flow through the chamber is substantially uniform and unidirectional. The holding chamber comprises an opening sufficient to permit movement of the supports to and from the holding chamber and comprises a plurality of holding elements for holding the supports.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L9 ANSWER 5 OF 6 USPATFULL on STN

AN 2001:185473 USPATFULL

TI Substrate preparation process

IN Goldberg, Martin, San Jose, CA, United States  
Diggelman, Martin, Arlesheim, Switzerland  
Hubbell, Earl, Mountain View, CA, United States  
McGall, Glenn, Mountain View, CA, United States  
Ngo, Nam Quoc, Campbell, CA, United States  
Morris, MacDonald, San Jose, CA, United States  
Yamamoto, Mel, Fremont, CA, United States  
Tan, Jennifer, Newark, CA, United States  
Rava, Richard P., San Jose, CA, United States

PA Affymetrix, Inc., Santa Clara, CA, United States (U.S. corporation)

PI US 6307042 B1 20011023

AI US 1999-244568 19990204 (9)

RLI Continuation of Ser. No. US 1996-634053, filed on 17 Apr 1996, now patented, Pat. No. US 5959098

DT Utility

FS GRANTED

EXNAM Primary Examiner: Riley, Jezia

LREP Banner & Witcoff, Ltd.

CLMN Number of Claims: 10

ECL Exemplary Claim: 1

DRWN 22 Drawing Figure(s); 20 Drawing Page(s)

LN.CNT 2059

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB The present invention provides novel processes for the large scale preparation of arrays of **polymer** sequences wherein each **array** includes a plurality of different, positionally distinct **polymer** sequences having known monomer sequences. The methods of the invention combine high throughput process steps with high resolution photolithographic techniques in the manufacture of polymer arrays.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L9 ANSWER 6 OF 6 USPATFULL on STN

AN 1999:117669 USPATFULL

TI Substrate preparation process

IN Goldberg, Martin, San Jose, CA, United States  
Diggelman, Martin, Arlesheim, Switzerland  
Hubbell, Earl, Mountain View, CA, United States  
McGall, Glenn, Mountain View, CA, United States  
Ngo, Nam Quoc, Campbell, CA, United States  
Morris, Macdonald, San Jose, CA, United States  
Yamamoto, Mel, Fremont, CA, United States  
Tan, Jennifer, Newark, CA, United States  
Rava, Richard P., San Jose, CA, United States

PA Affymetrix, Inc., Santa Clara, CA, United States (U.S. corporation)

PI US 5959098 19990928

AI US 1996-634053 19960417 (8)

DT Utility  
FS Granted  
EXNAM Primary Examiner: Fredman, Jeffrey  
LREP Townsend & Townsend & Crew  
CLMN Number of Claims: 15  
ECL Exemplary Claim: 1  
DRWN 22 Drawing Figure(s); 20 Drawing Page(s)  
LN.CNT 2111

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB The present invention provides novel processes for the large scale preparation of arrays of **polymer** sequences wherein each **array** includes a plurality of different, positionally distinct **polymer** sequences having known monomer sequences. The methods of the invention combine high throughput process steps with high resolution photolithographic techniques in the manufacture of polymer arrays.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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L2 141 S L1 AND SUPPORT  
L3 96 S L2 AND INLET  
L4 92 S L3 AND OUTLET  
L5 77 S L4 AND CHEMICAL  
L6 18 S L5 AND SUPPORT? (6A) CHAMBER?  
L7 18 DUP REM L6 (0 DUPLICATES REMOVED)  
L8 6 S L5 AND ARRAY (15A) POLYMER?  
L9 6 DUP REM L8 (0 DUPLICATES REMOVED)

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L3 96 S L2 AND INLET  
L4 92 S L3 AND OUTLET  
L5 77 S L4 AND CHEMICAL  
L6 18 S L5 AND SUPPORT? (6A) CHAMBER?  
L7 18 DUP REM L6 (0 DUPLICATES REMOVED)  
L8 6 S L5 AND ARRAY (15A) POLYMER?  
L9 6 DUP REM L8 (0 DUPLICATES REMOVED)  
L10 166 S L1 NOT L7  
L11 161 S L10 NOT L9  
L12 161 DUP REM L11 (0 DUPLICATES REMOVED)  
L13 135 S L12 AND (STRIP OR PLATE OR FLAT GLASS)  
L14 135 S L13 AND CHEMICAL?  
L15 87 S L14 AND SYNTHESI?  
L16 54 S L15 AND INLET  
L17 53 S L16 AND OUTLET  
L18 53 S L17 AND STEP?  
L19 49 S L1 AND SYNTHES? (4A) ARRAY?  
L20 71558 S ARRAY AND CHAMBER?  
L21 1160 S L20 AND FLOW CELL?  
L22 854 S L21 AND SUPPORT  
L23 514 S L22 AND INLET?  
L24 371 S L23 AND OUTLET  
L25 115 S L24 AND SYNTHES? (3A) ARRAY  
L26 62 S L25 AND MOUNT?  
L27 62 DUP REM L26 (0 DUPLICATES REMOVED)  
L28 62 S L27 NOT L18  
L29 43 S L28 AND DROP?

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